

Magnetic Tunneling Junctions: History

1974 Slonczewski - concept proposed

1975 Juliere - first demonstration (CNR-France)

Fe/Ge/Co, $\Delta R/R \sim 14\%$ at 4.2 K

1982 Maekawa and Gafvert (IBM post-docs)

Ni/NiO/Ni, Fe, Co, $\Delta R/R \sim 0.4-2\%$ at 4.2 K

1990~1993 Miyazaki et al. (Tohoku University)

NiFe/Al-Al₂O₃/Co, $\Delta R/R \sim 2.7\%$ at room temperature (RT)

1995 Miyazaki et al. (Tohoku University) - first large MR at RT

Fe/Al-Al₂O₃/Co, $\Delta R/R \sim 18\%$ at RT

1995 Moodera et al. (MIT) - large RT MR

Co-Fe/Al-Al₂O₃/Co, $\Delta R/R \sim 10\%$ at RT

1995 Gallagher and Parkin – proposal for MRAM using MTJs

1996 Parkin et al. - large RT MR

>25% in shadow masked and patterned junctions; reproducible

1998 Parkin et al. - extraordinarily large RT MR; high thermal stability

>35% in sub-micron junctions; >47% in shadow masked junctions

specific resistances ~ 60 to $>10^9 \Omega(\mu\text{m})^2$; thermal stability ($>300^\circ\text{C}$)

1999-2000 Scheuerlein et al. – First MTJ MRAM demonstration

<3 ns read and write

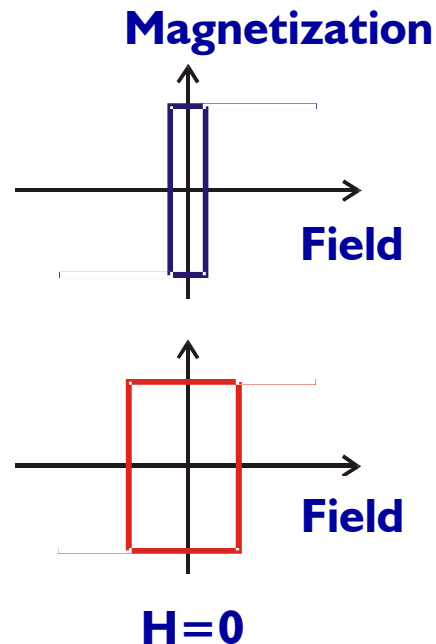
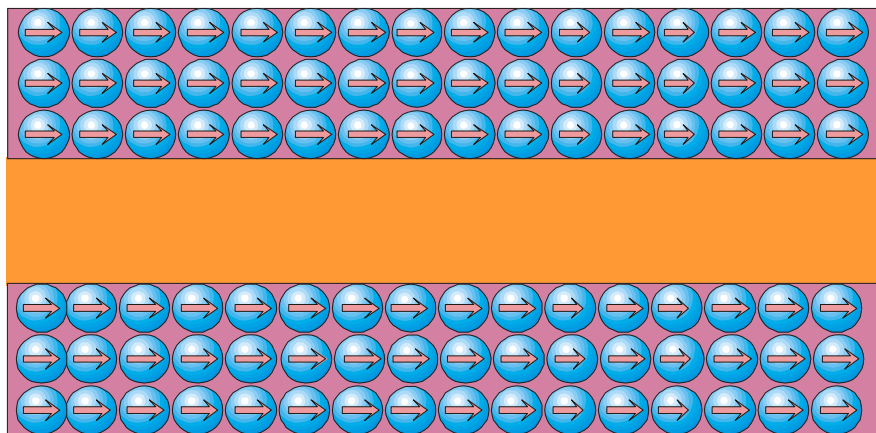
2001-2003 Parkin et al. – giant MR using novel tunnel barrier ($>220\%$ at RT)

2002 Durlam et al. – 1 Mbit MRAM in 0.6 μm technology

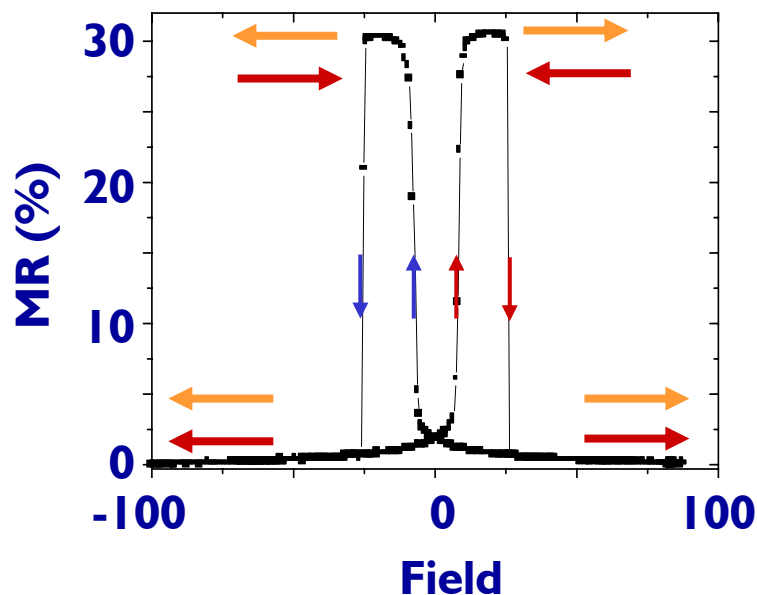
2003 Sitaram et al.; Bette et al. – 128 kbit MRAM core in 0.18 μm technology



Simplest MTJ: Hard-Soft



MTJ comprised of two FM layers with different coercivities

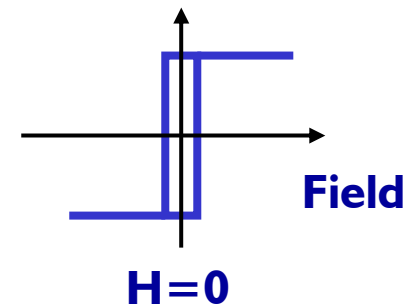
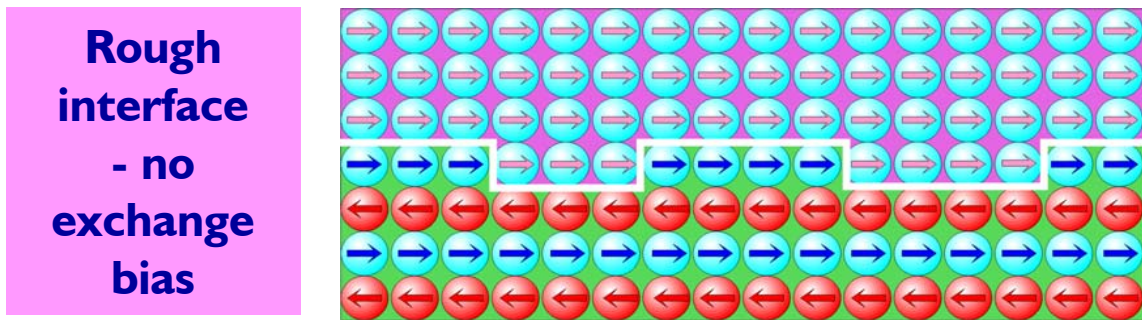
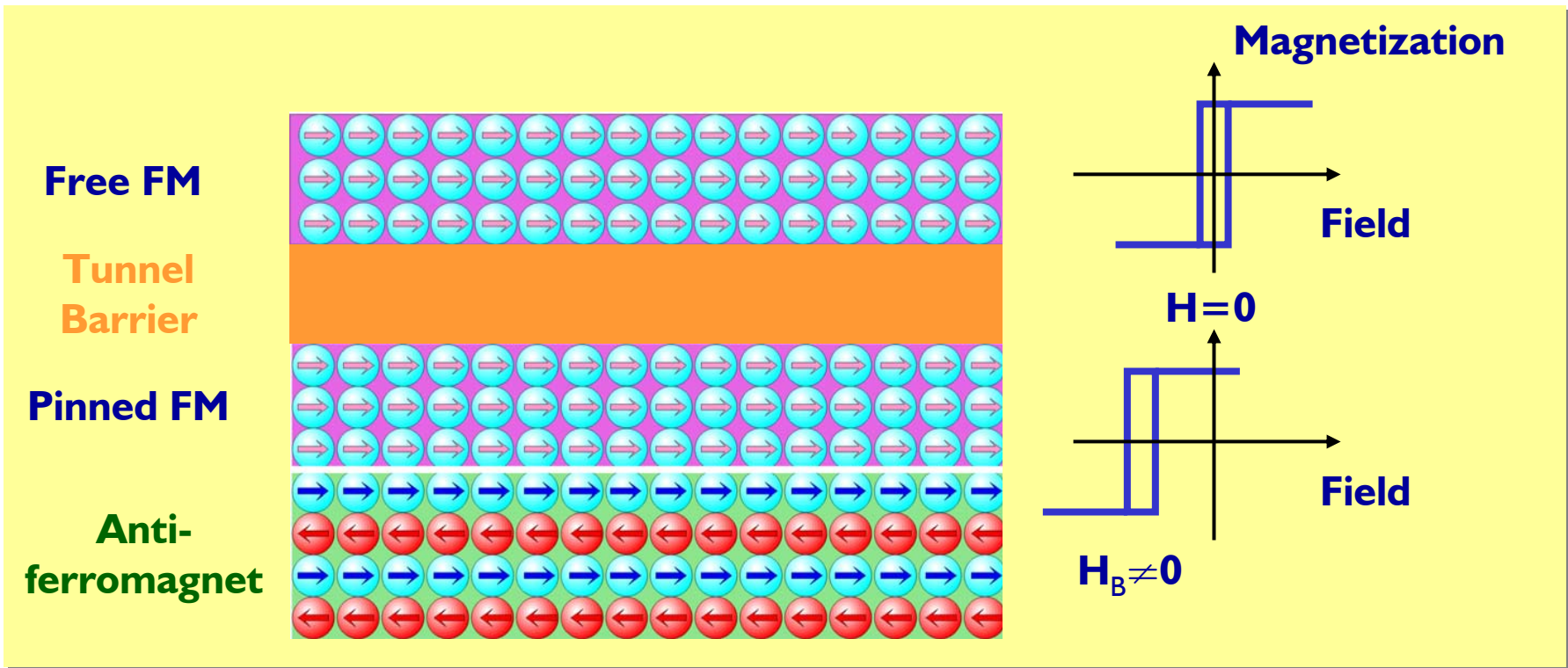


Pd
80Å $\text{Co}_{84}\text{Fe}_{16}$
16Å Al-I80s
24Å $\text{Co}_{84}\text{Fe}_{16}$
100Å $\text{Ir}_{22}\text{Mn}_{78}$
200Å Ti

Problems:

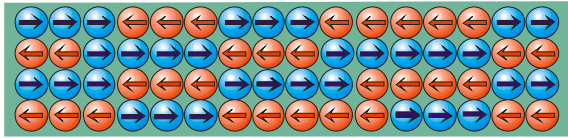
- difficult to control magnetics:
- difficult to find FM layer with very high H_c and S

Spin Valve Structure using Exchange Bias

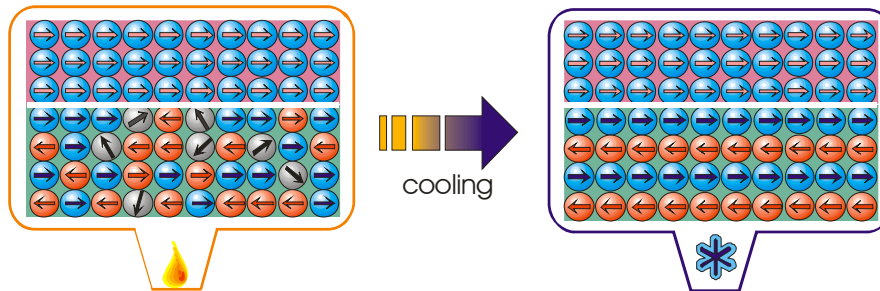


Establishing Exchange Bias

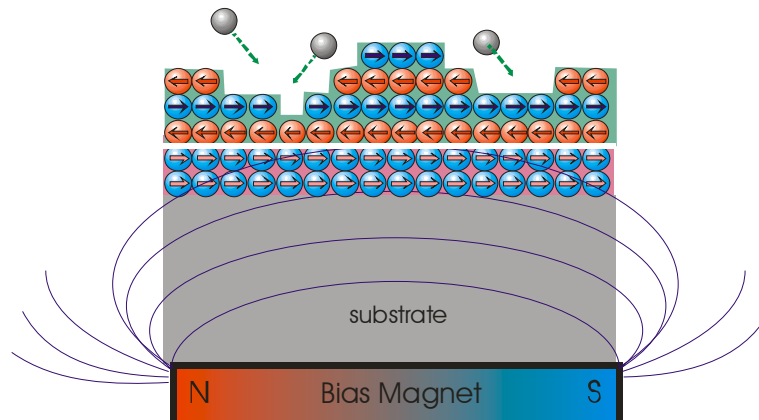
An antiferromagnet grown in the absence of a magnetic field has no long-range magnetic order



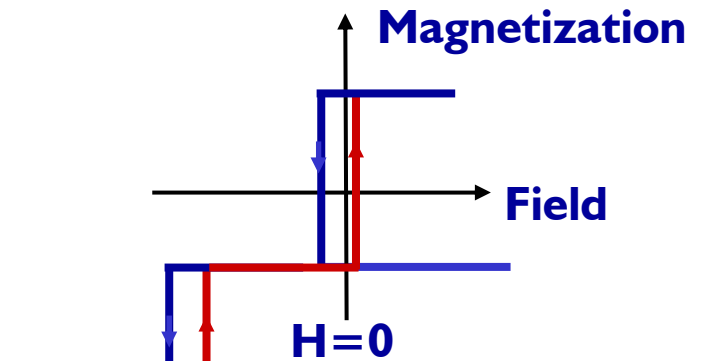
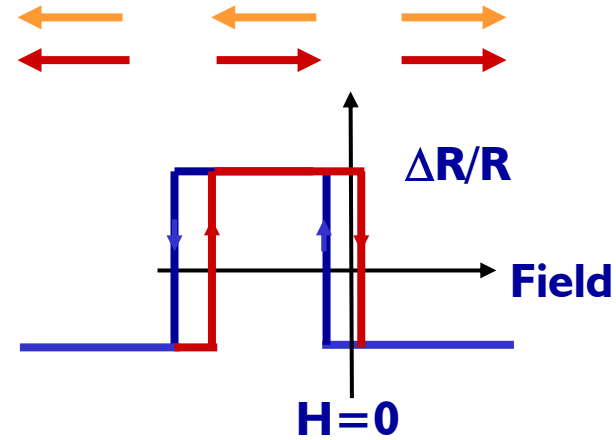
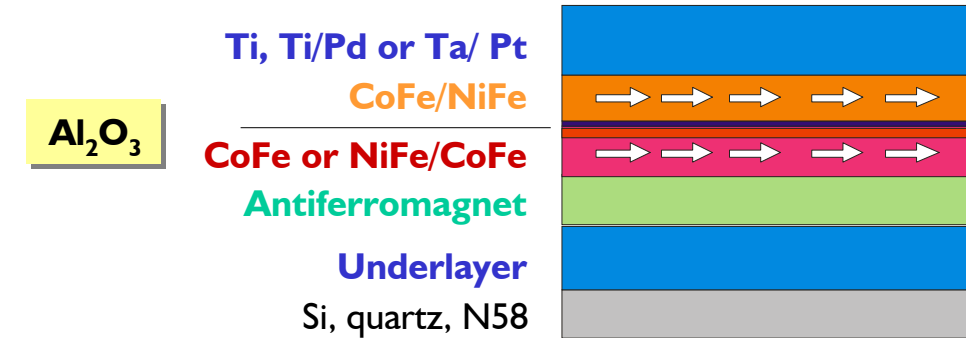
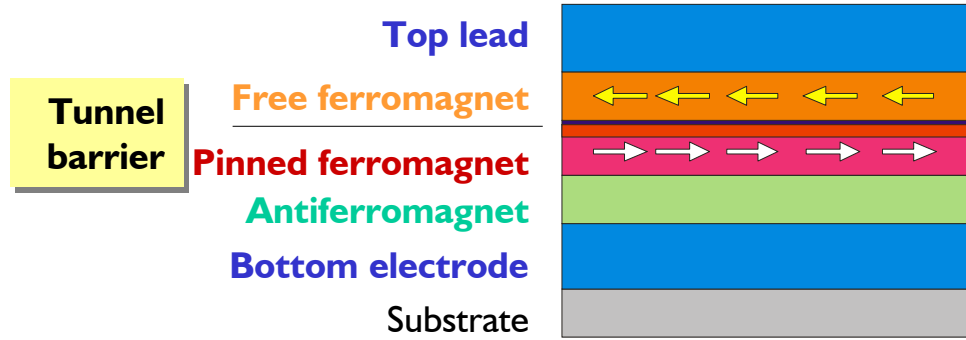
A disordered antiferromagnet layer adjacent to a ferromagnetic layer may be magnetically ordered by heating above its blocking temperature and subsequently cooling



Antiferromagnet film deposition onto a ferromagnetic layer biased by an external applied field will yield a uniformly antiferromagnetically ordered layer

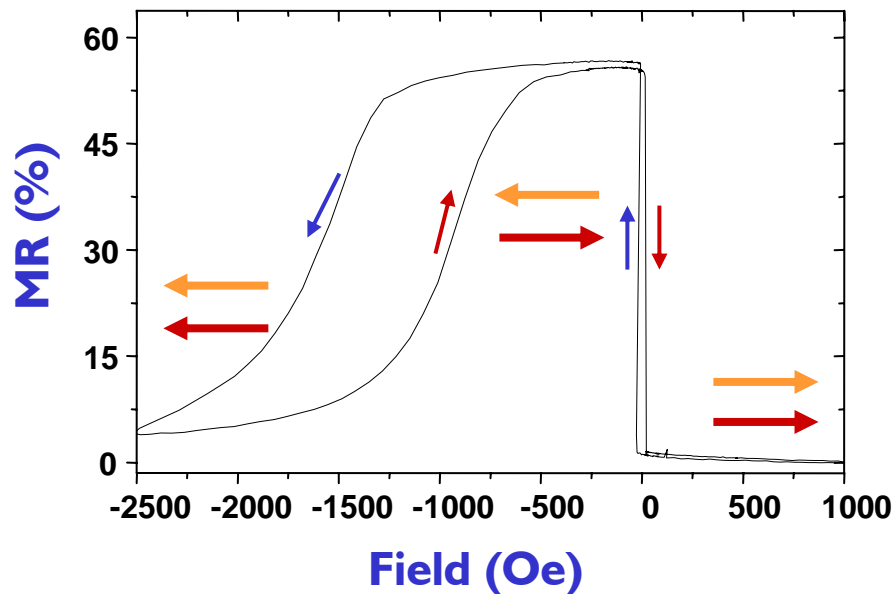


Exchange-Biased Magnetic Tunnel Junction



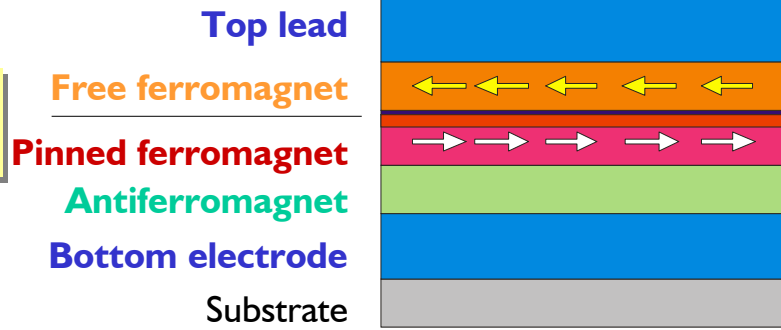
MR ~ 50%

Switching field of free layer ~ 3 Oe

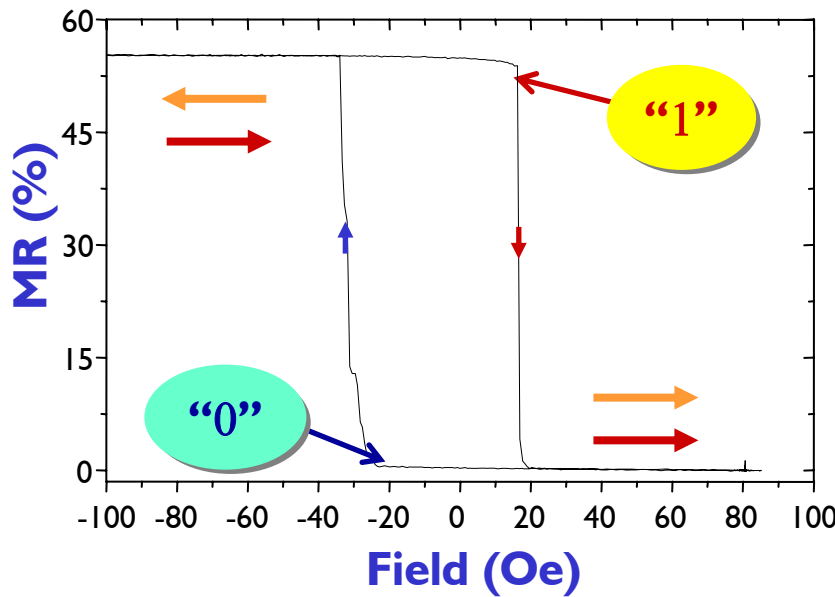
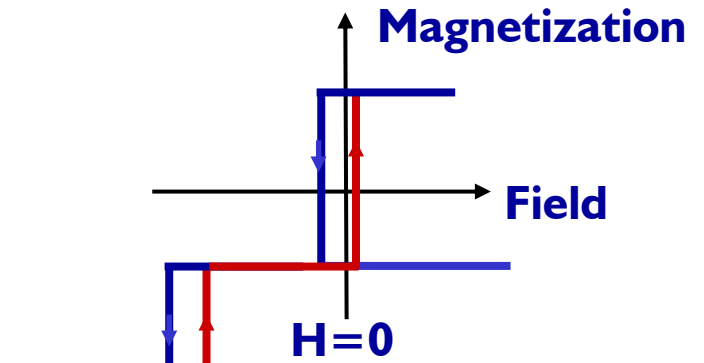
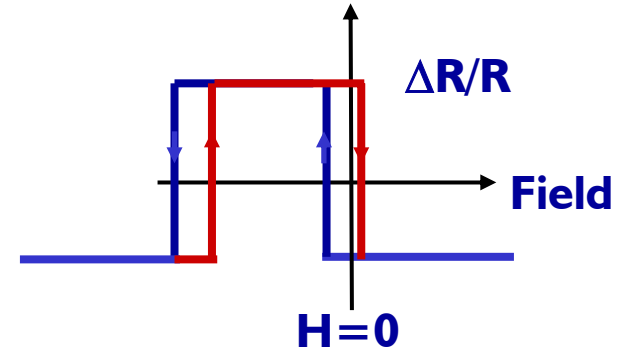
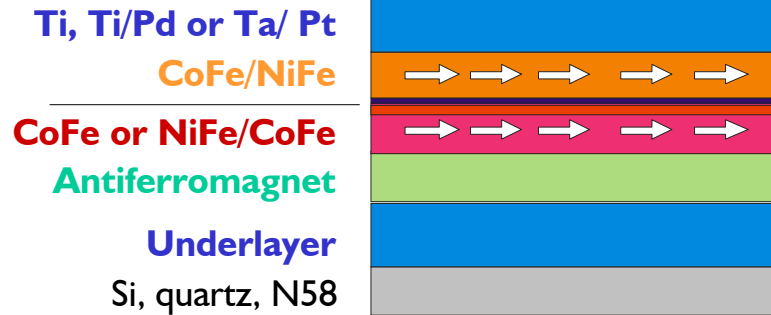


Exchange-Biased Magnetic Tunnel Junction (MTJ)

Tunnel barrier

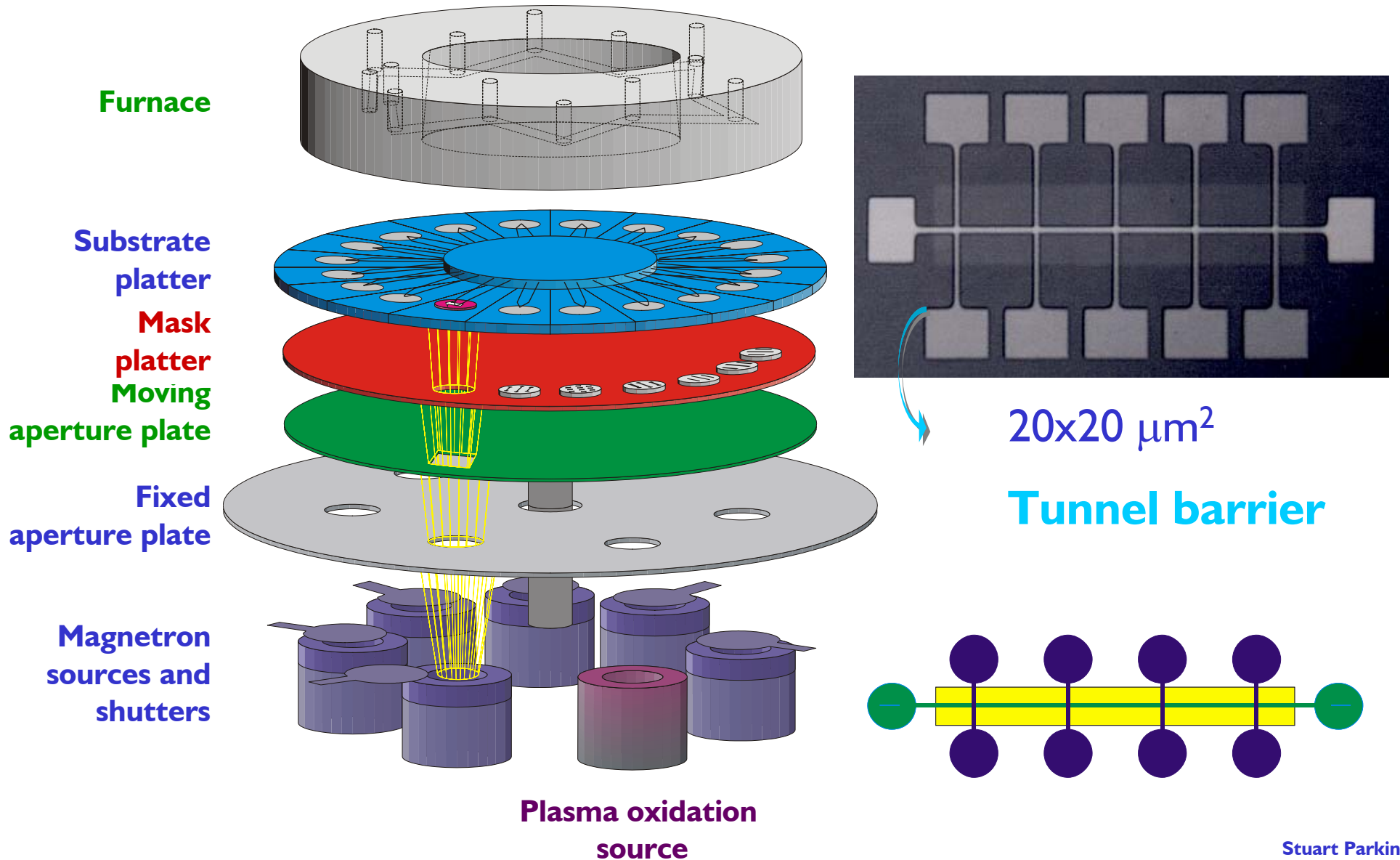


Al_2O_3

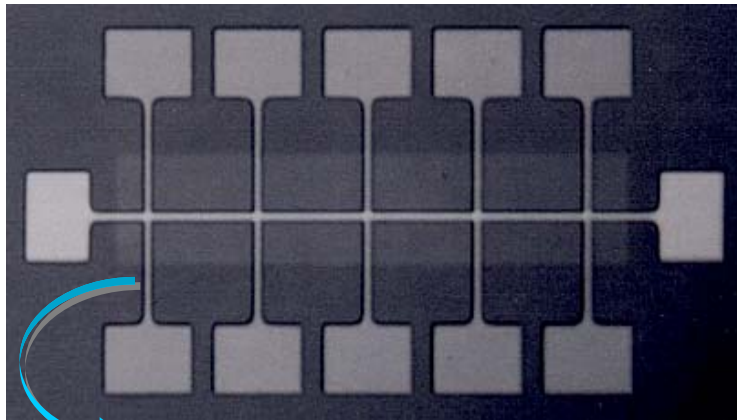
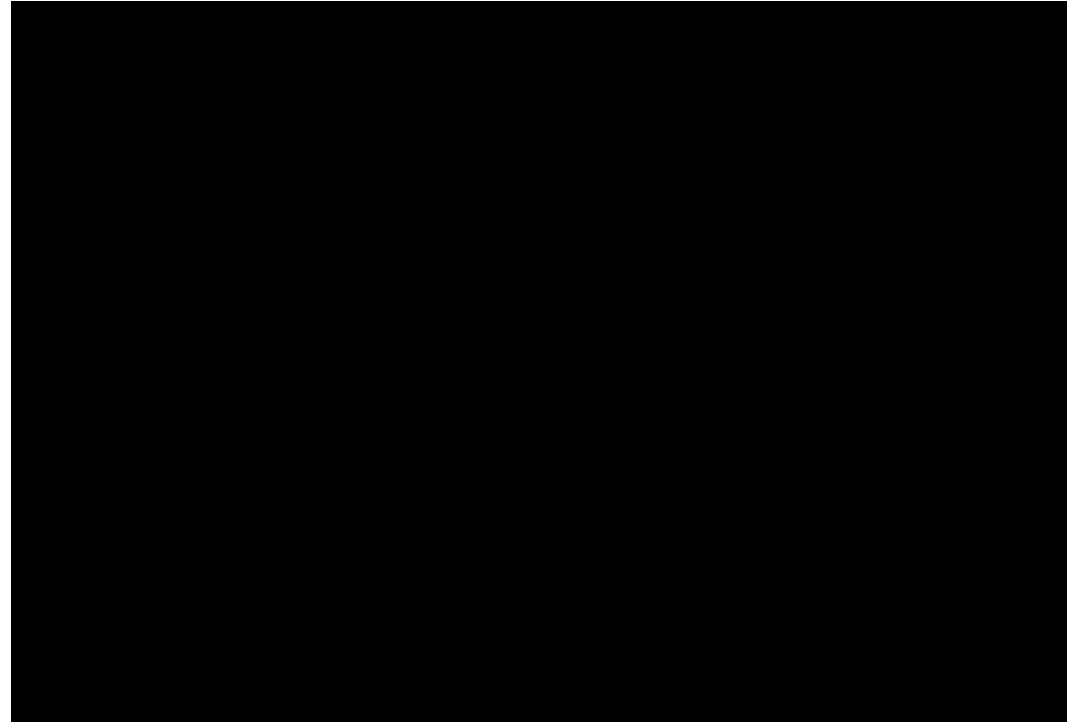
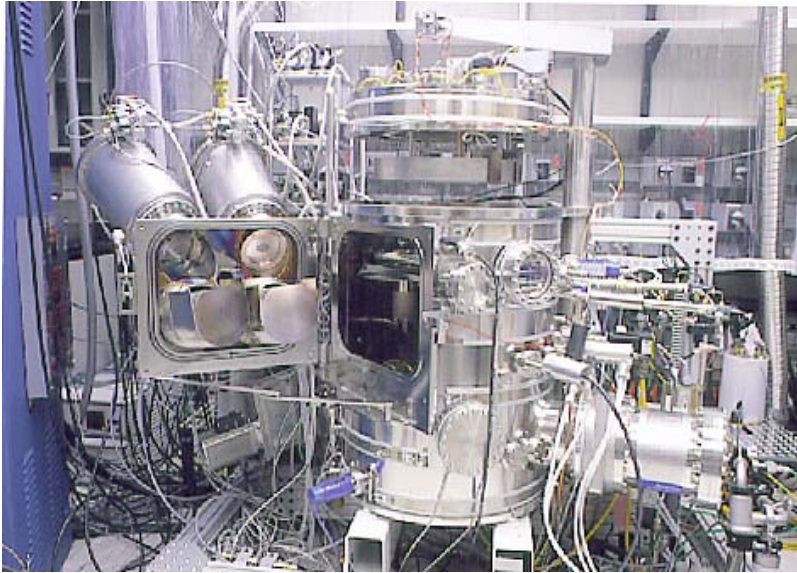


Non-Volatile Memory!

Shadow-Masked Structures Prepared by Sputter Deposition



Shadow-masked MTJs prepared by sputter deposition



20x20 μm^2

Tunnel barrier

Lecture II: Magnetic Tunnel Junctions and MRAM

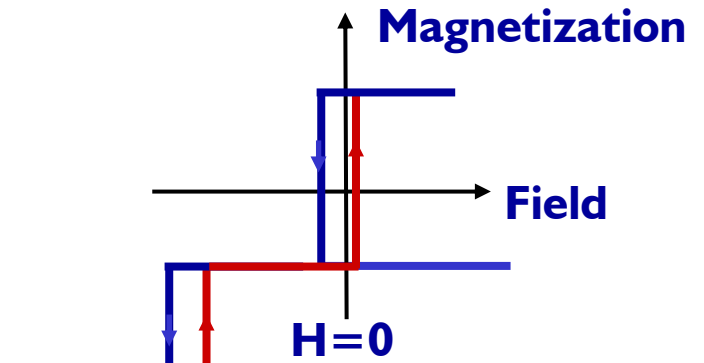
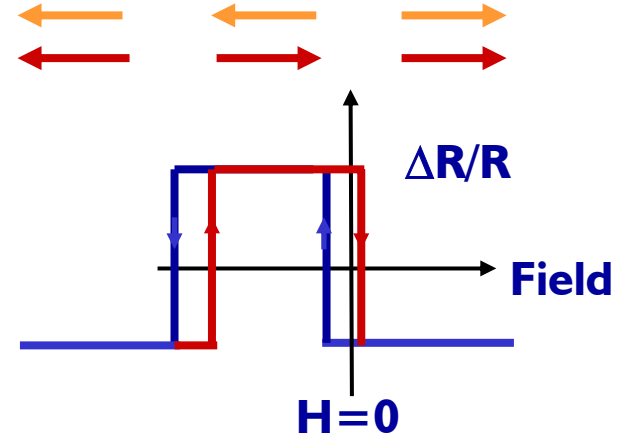
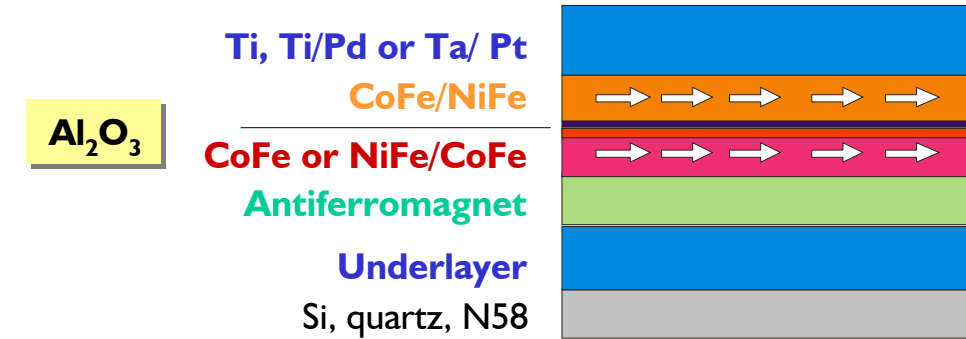
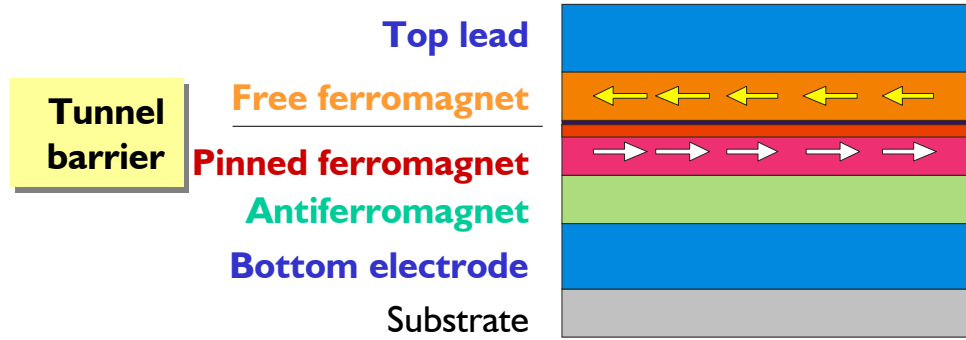
Stuart Parkin

IBM Almaden Research Center, San Jose, California

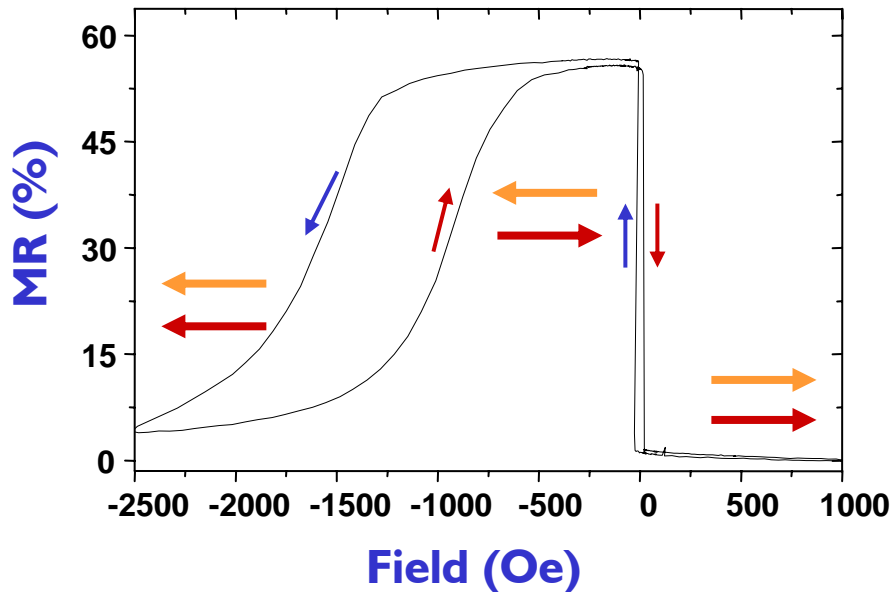
- ◆ **Magnetic tunnel junctions**
 - ◆ Magnetic engineering
- ◆ **Spin polarization of tunneling current**
 - ◆ $\sim 50\%$ for 3d transition metal ferromagnets/ Al_2O_3
- ◆ **Magnetic Random Access Memory**
 - ◆ Attractive: Non-volatile, dense and high-speed
- ◆ **Magnetic Tunnel Transistor [Lecture 3]**
 - ◆ Hot electron spin injection into GaAs and Si
 - ◆ 3,500% change in collector current $\rightarrow \sim 100\%$ spin polarized current
 - ◆ Optical detection of spin polarized current using QW light emitting diode

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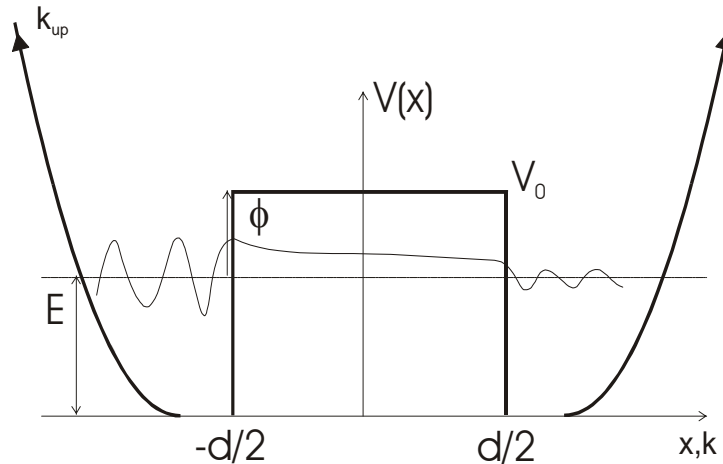
Exchange-Biased Magnetic Tunnel Junction



MR ~ 50%
Switching field of free layer ~ 3 Oe



Exact Free Electron Model of Tunneling



Schrödinger equation

$$-\frac{\hbar^2}{2m} \frac{d^2\psi(x)}{dx^2} + V(x) \cdot \psi(x) = E \cdot \psi(x)$$

$$k = \sqrt{\frac{2mE}{\hbar^2}}$$

$$\kappa = \sqrt{\frac{2m(V_0 - E)}{\hbar^2}}$$

$$\psi(x) = e^{ikx} + R \cdot e^{-ikx}$$

$$\psi(x) = A \cdot e^{-\kappa x} + B \cdot e^{\kappa x}$$

$$\psi(x) = T \cdot e^{-ikx}$$

Flux transmission given by:

$$|T|^2 = \frac{(2k\kappa)^2}{(k^2 + \kappa^2)^2 \sinh^2 2\kappa d + (2k\kappa)^2}$$

Tunneling Matrix elements

- Tunneling is a quantum mechanical phenomenon
 - From basic quantum mechanics, the barrier height (Φ), width (d) and electron energy (k) determine the transmission probability
- Exponential decrease with barrier thickness and height

$$T \sim \frac{16k_1k_2\kappa \exp(-2d\kappa)}{[\kappa(k_1 + k_2)]^2 + (\kappa^2 - k_1k_2)^2}$$

$$\kappa = \sqrt{(2m/\hbar^2)(\Phi - E_f)}$$

